a contact portion for electrical connection to the TFT is disposed at a part of the pixel electrode; and

an insulating layer is embedded in a recess portion provided at the contact portion,

wherein the insulating layer comprises a light absorbing layer comprising a resin in which a pigment or a carbon-based material is contained.

2. (Three Times Amended) A display device comprising a pixel matrix circuit constituted by a plurality of pixels each including at least one TFT and a pixel electrode connected to the TFT, wherein:

the pixel electrode includes a lamination structure of a first metal layer and a second metal layer; and

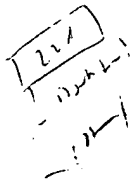
an insulating layer is put between the first metal layer and the second metal layer at a contact portion where the first metal layer is connected with the TFT,

wherein the insulating layer comprises a light absorbing layer comprising a resin in which a pigment or a carbon-based material is contained.

3. (Three Times Amended) A display device comprising a pixel matrix circuit constituted by a plurality of pixels each including at least one TFT and a pixel electrode connected to the TFT, wherein:

the pixel electrode includes a lamination structure of a first metal layer and a second metal layer;

an insulating layer is embedded in a recess portion disposed on the first metal layer; and



the second metal layer is disposed so as to cover the first metal layer and the insulating film,

wherein the insulating layer comprises a light absorbing layer comprising a resin in which a pigment or a carbon-based material is contained.

8. (Twice Amended) An electronic equipment comprising a display device according to claim 1 as a display.

16. (Amended) An electronic device having at least one active matrix type liquid crystal panel, said liquid crystal panel comprising:

a substrate having an insulating surface;

an active matrix circuit formed over said substrate comprising a plurality of pixel electrodes, a plurality of switching elements for switching said pixel electrodes, respectively, an interlayer insulating film formed over said plurality of switching elements wherein each of said plurality of pixel electrodes is formed on said interlayer insulating film and electrically connected to the respective switching element through a contact hole of said interlayer insulating film; and

a driving circuit comprising a plurality of thin film transistors formed over said substrate for driving said active matrix circuit,

wherein a depression of said pixel electrode formed over said contact hole is filled with a light absorbing insulating material,

wherein the light absorbing insulating material comprises a resin in which a pigment or a carbon-based material is contained.

42. (Amended) An electronic device having at least one active matrix type display device comprising:

at least one switching element;

at least one interlayer insulating film formed over said switching element;

a pixel electrode formed on said interlayer insulating film and electrically connected to said switching element through a contact hole of said interlayer insulating film;

a light absorbing insulating material formed in a depression of said pixel electrode over said contact hole,

wherein the light absorbing insulating material comprises a resin in which a pigment or a carbon-based material is contained.

48. (Amended) An electronic device having at least one active matrix type display device comprising:

at least one switching element;

at least one interlayer insulating film formed over said switching element;

a pixel electrode formed on said interlayer insulating film and electrically connected to said switching element through a contact hole of said interlayer insulating film;

a light absorbing insulating material formed in a depression of said pixel electrode over said contact hole,

wherein said insulating material is a light absorbing material comprising a resin in which a pigment or a carbon-based material is contained.